

# Nanoscale Contact Formation Dynamics

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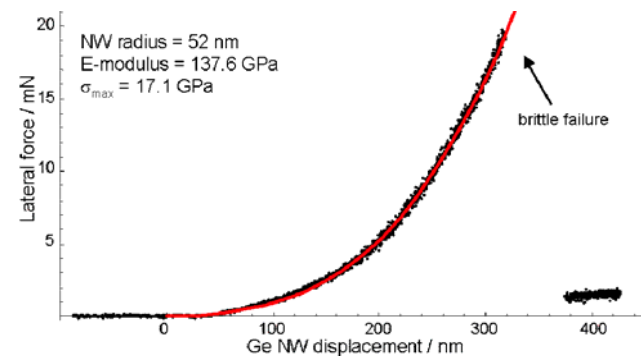
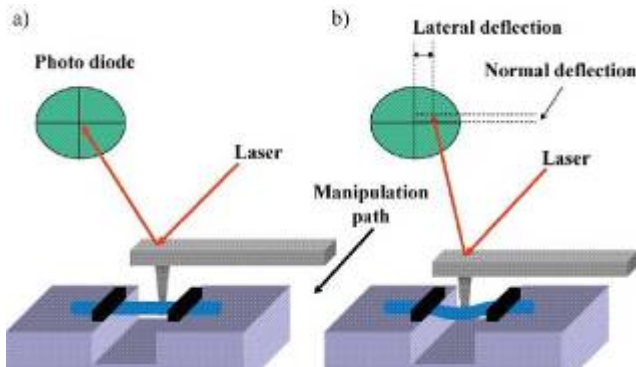
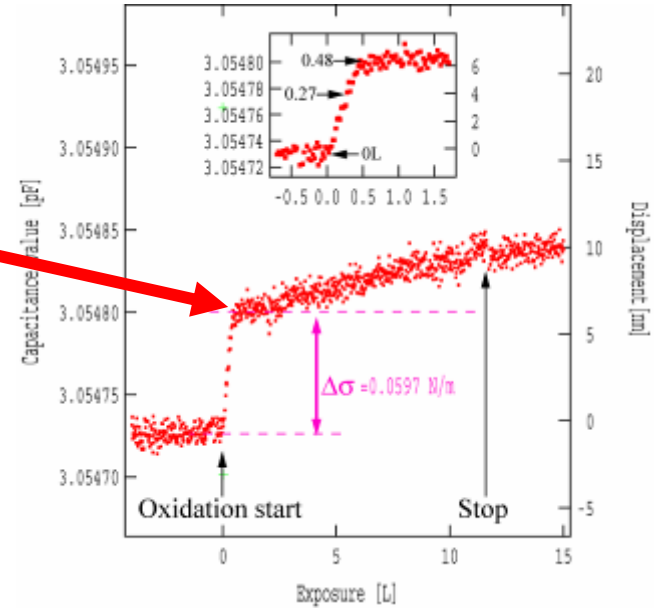
*The School of Chemistry &*

*Centre for Research on Adaptive Nanostructures and Nanodevices (CRANN)*

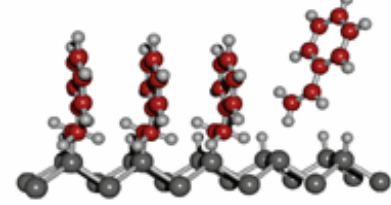
*Trinity College Dublin*

*Dublin 2, Ireland*

# Other Research Activities



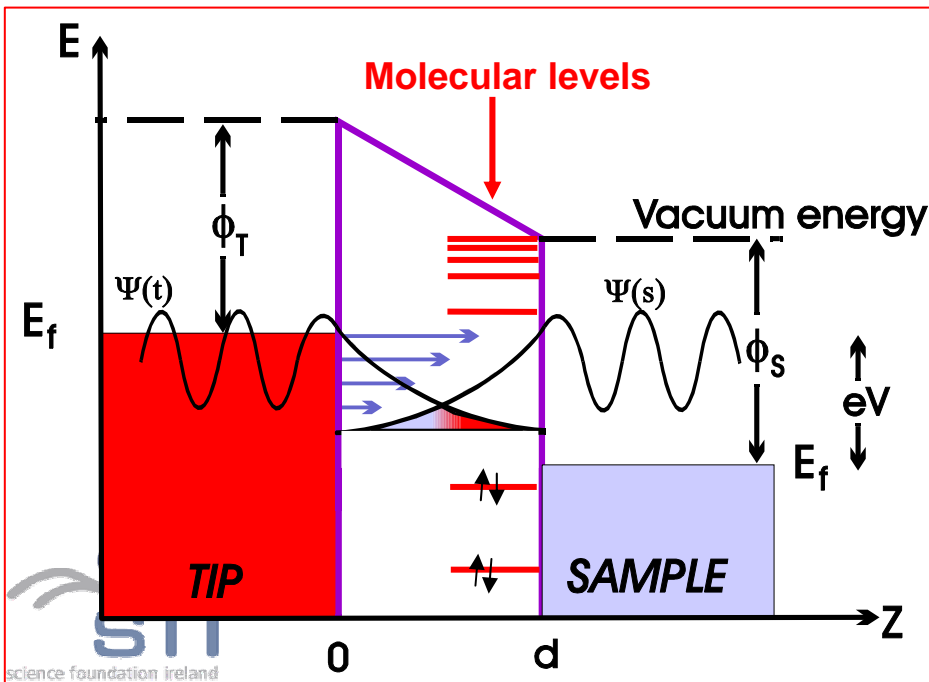
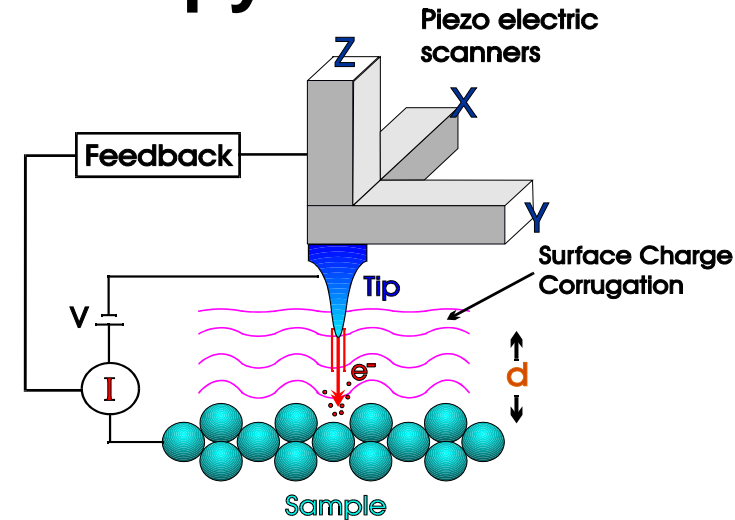
# Why Contacts?



- **The success of future nanoscale devices is critically dependent on gaining an atom-level understanding of contact formation**
  - How are electronic properties of the molecule/nanomaterial affected by contact?
  - How does the molecule/material respond when contact is established?
  - What role is played by the contact metal?
  - Can we predict the conductance of nanoscale systems?
- **How can one go about answering these types of questions?**
  - Approach: develop new methodologies based on cryogenic STM

# Scanning Tunneling Microscopy

- Overlap of tip and sample wavefunctions
- Applied bias defines the energy window sampled
- Study HOMO and LUMO levels



$$I_t \propto \rho_s(0, E_F) e^{-\phi^{1/2} z}$$

LDOS at location  $z$  and energy  $E$

$$\rho(z, E) = \frac{1}{\epsilon} \sum_{E_n = E - \epsilon}^E |\psi_n(z)|^2$$

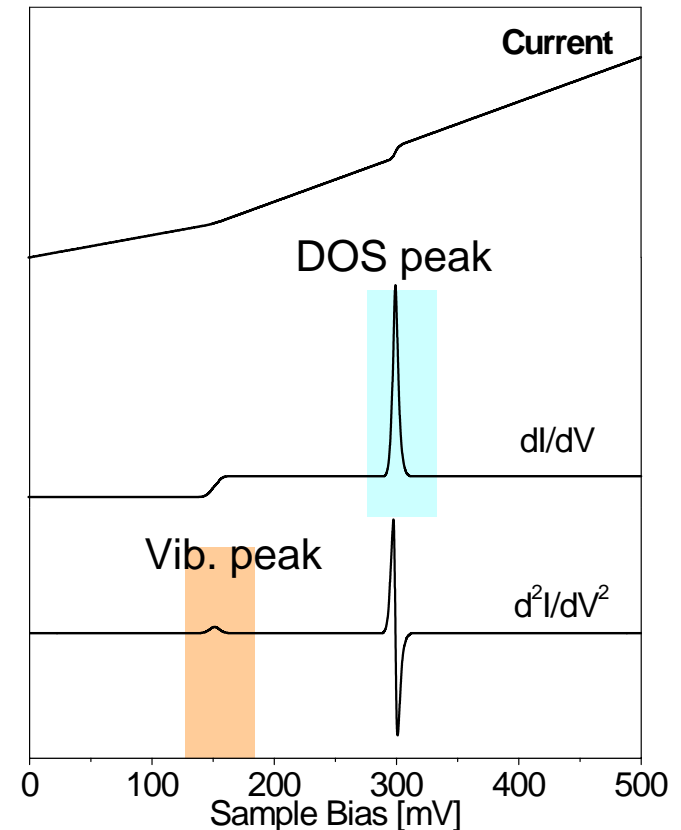
# DOS, Molecular Vibrations, and Barrier-height

$$I(V) \propto \int_{E_F}^{E_F+eV} DOS(E) T(E, V) dE$$

$$\frac{dI}{dV} \Rightarrow \text{peaks}^{DOS}$$

$$\frac{d^2I}{dV^2} \Rightarrow \frac{d}{dV}(DOS) + \text{peaks}^{ETS}$$

$$I \propto \exp(-A\sqrt{\phi Z}) \Rightarrow \phi \propto \left( -\frac{dI/dZ}{IA} \right)^2$$



In principle STM can provide significant insights

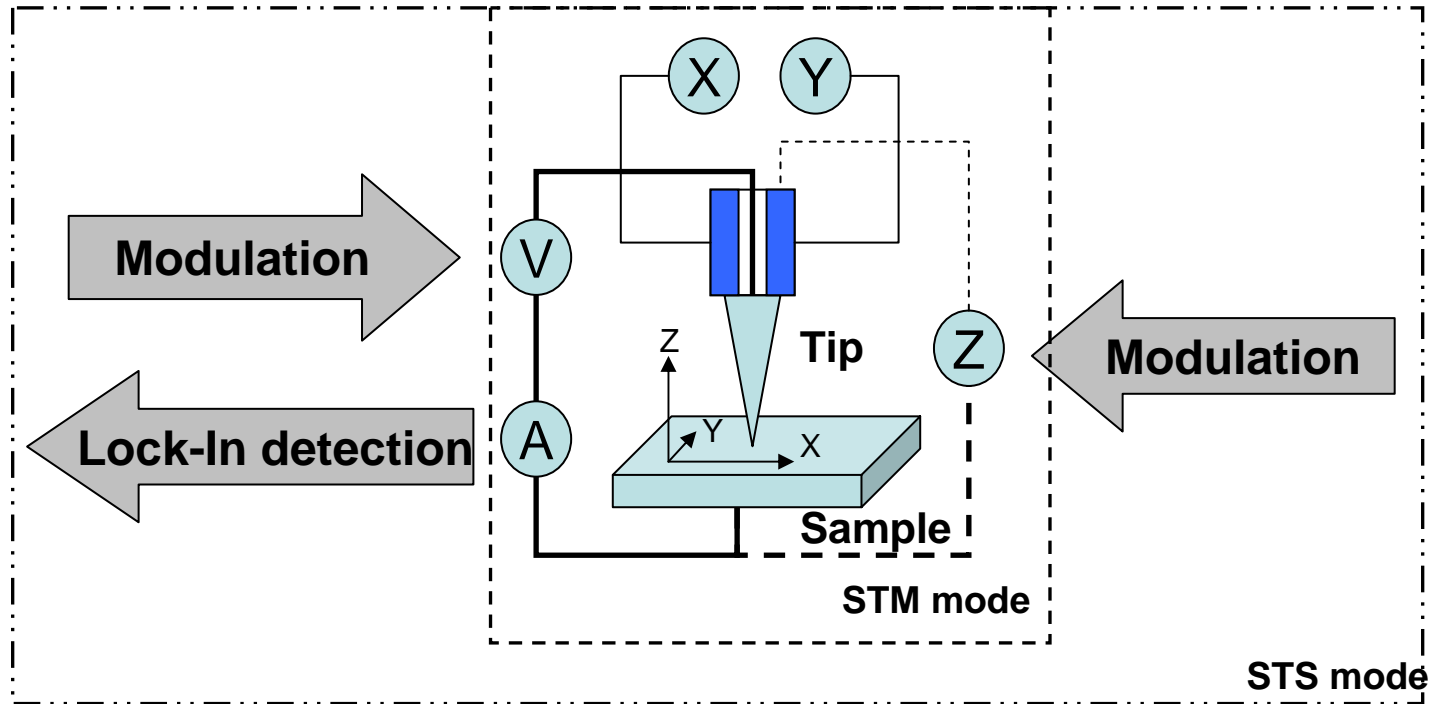
Not delivered in practice, poor correlation of properties with contact formation, no ability to account for forces involved



# Strategy

- Separate the electronic and mechanical effects:
  - Record detailed changes in the electronic and vibrational properties of molecule as probe approaches to contact
  - Measure forces experienced during contact  
(new technique, refer to as relaxation spectroscopy)
  - Study contacts with molecules and nanomaterials

# Scanning Tunnelling Spectroscopy (STS)



**Conventional STS measurements**

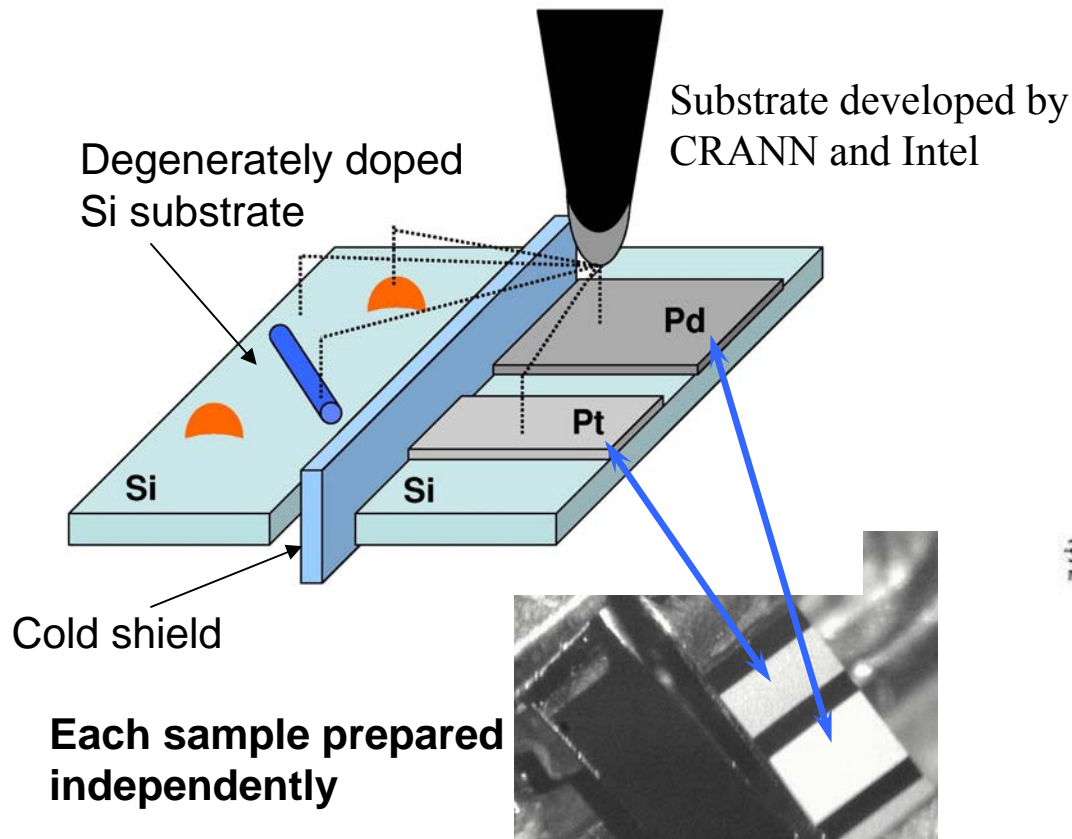
$$\begin{aligned} I(V) &|_{Z \text{ constant}} \\ dI/dV &|_{Z \text{ constant}} \\ d^2I/dV^2 &|_{Z \text{ constant}} \end{aligned}$$

$$\begin{aligned} I(Z) &|_{V \text{ constant}} \\ dI/dZ &|_{V \text{ constant}} \\ d^2I/dZ^2 &|_{V \text{ constant}} \end{aligned}$$

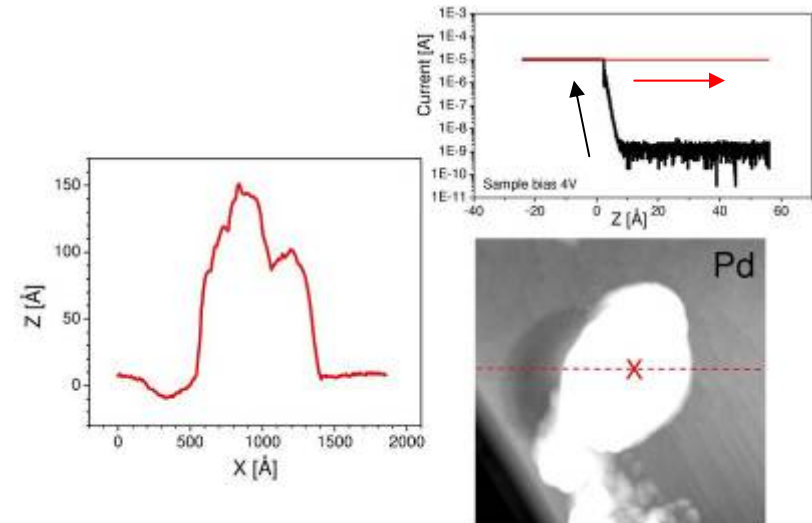
**Basis for force measurements**

Only for specific energy window defined by the applied bias

# Integrated Substrate\* for probe preparation



Metal-inking: drawing material from the surface onto the probe apex

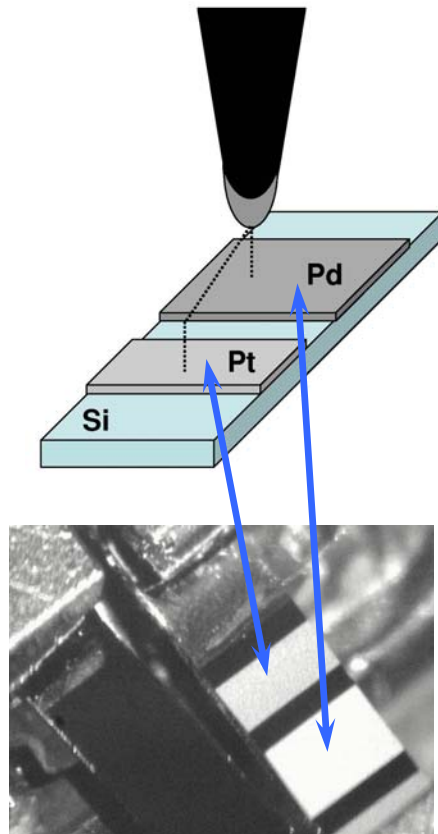


Metal-inking essential to control composition and electrical properties of probe  
Guarantees that bias maps onto the energy scale in STS measurements

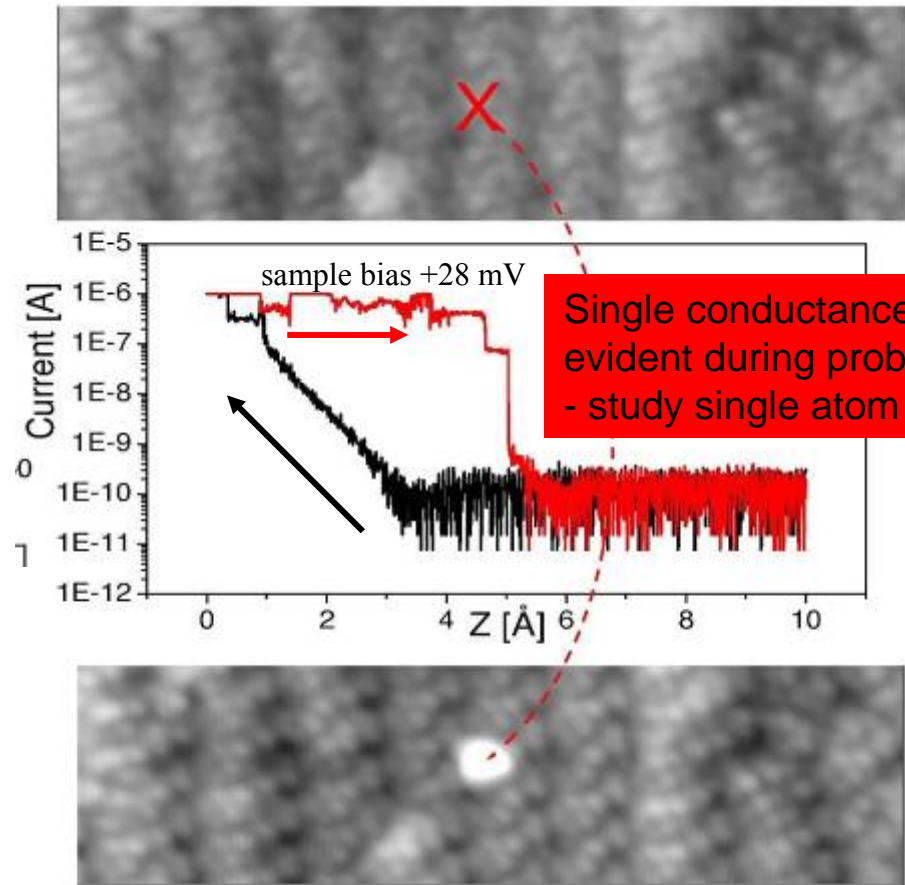


# Integrated Substrate for probe preparation

## Probe sharpening on Pd surface

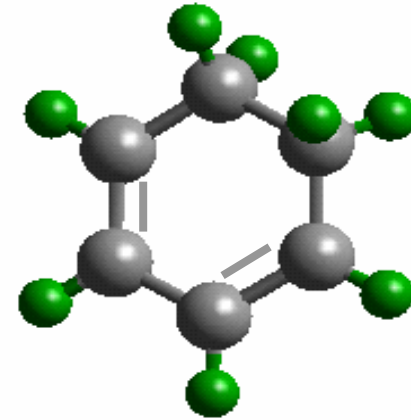
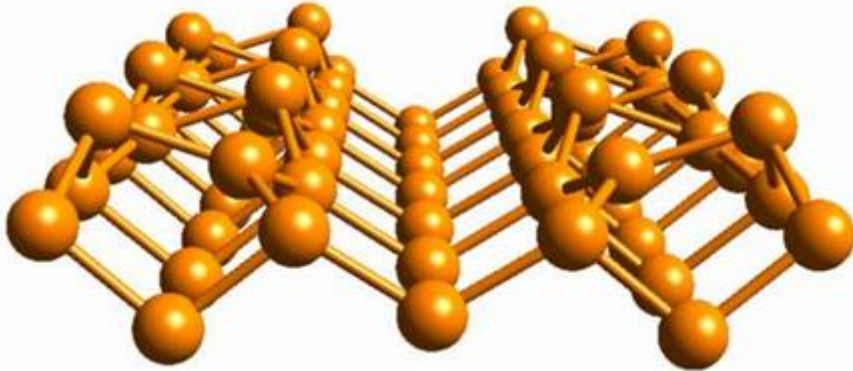


Top view

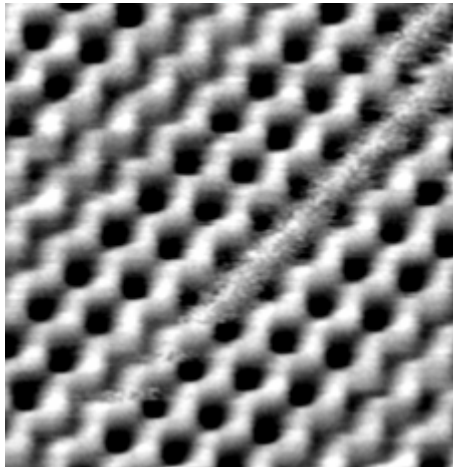


Characterize sharpened probe by STS and barrier height measurements on known samples

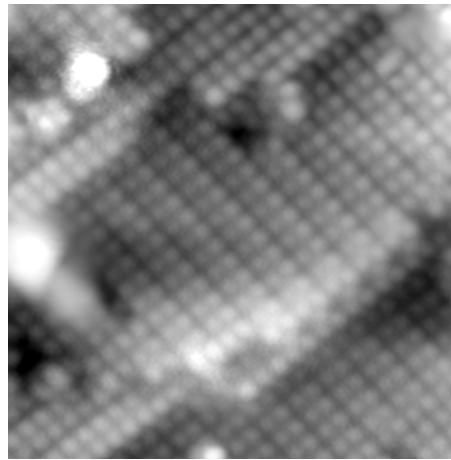
# Example A: Si(100) Substrate and Molecule



**1,3-cyclohexadiene  
(1,3-CHD)**



**Bare surface**



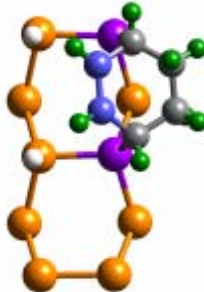
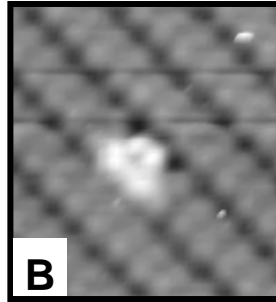
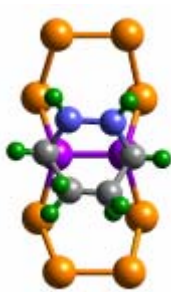
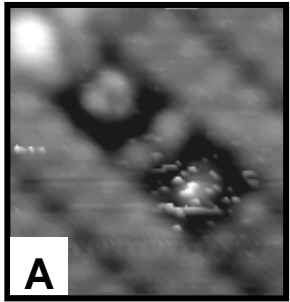
**H passivated**

**5 K STM image of Si(100)**

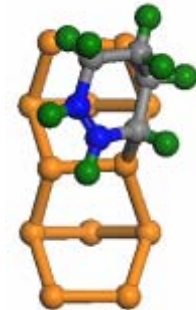
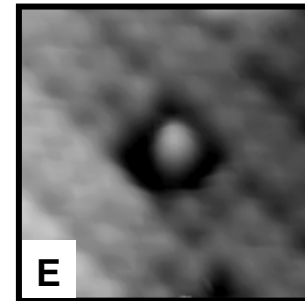
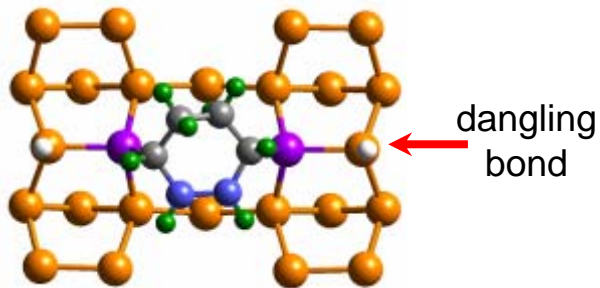
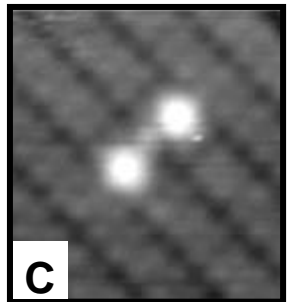
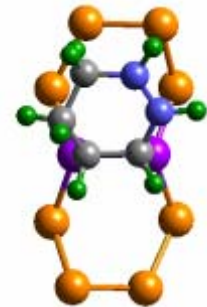
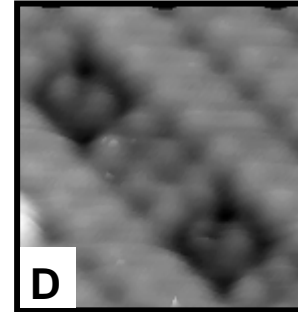
After reaction one C=C double bond remains and corresponds to the topographic maximum visible in STM (5 different possible configurations)

# 1,3-CHD on bare Si(100) surface

[4+2] Products



[2+2] Products



**Color Key:** Si C C=C H Si-C

Product identification based on location of single remaining C=C

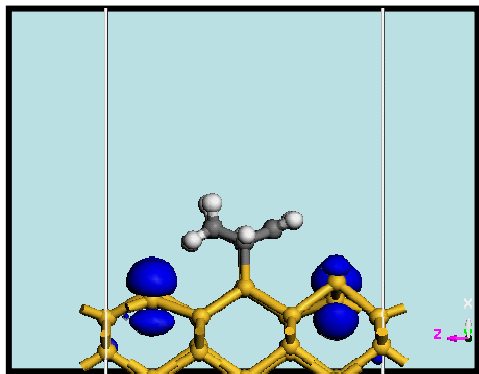
Always some noisy sites on surface

Empty state images: tunnelling into  $\pi^*$  level of C=C?

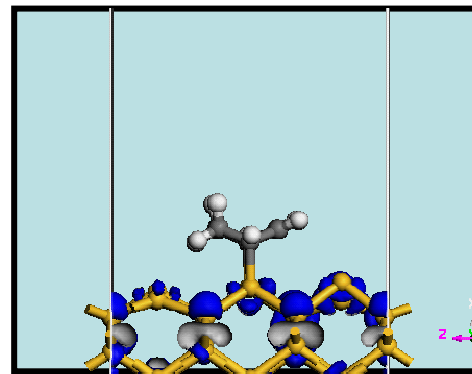
# Can't explain origin of STM contrast

- DFT reveals broadened  $\pi^*$  state at +3.5eV
- Broadened  $\pi^*$  does not extend appreciably below +2 eV

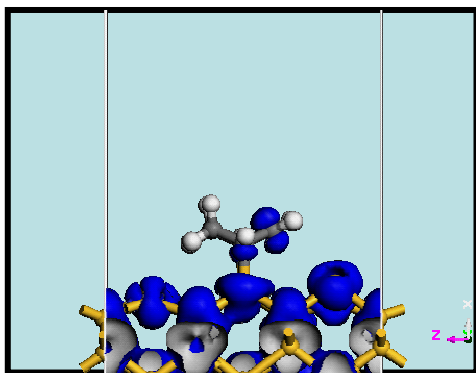
Bias +1.0eV



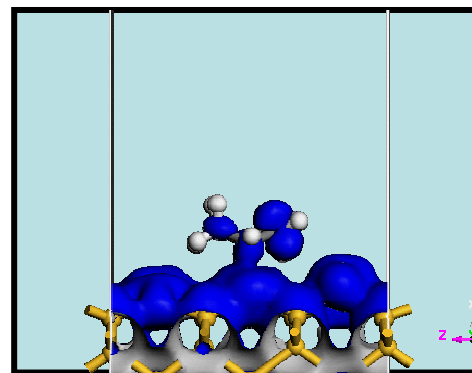
Energy window 0-1eV



Energy window 1-2eV

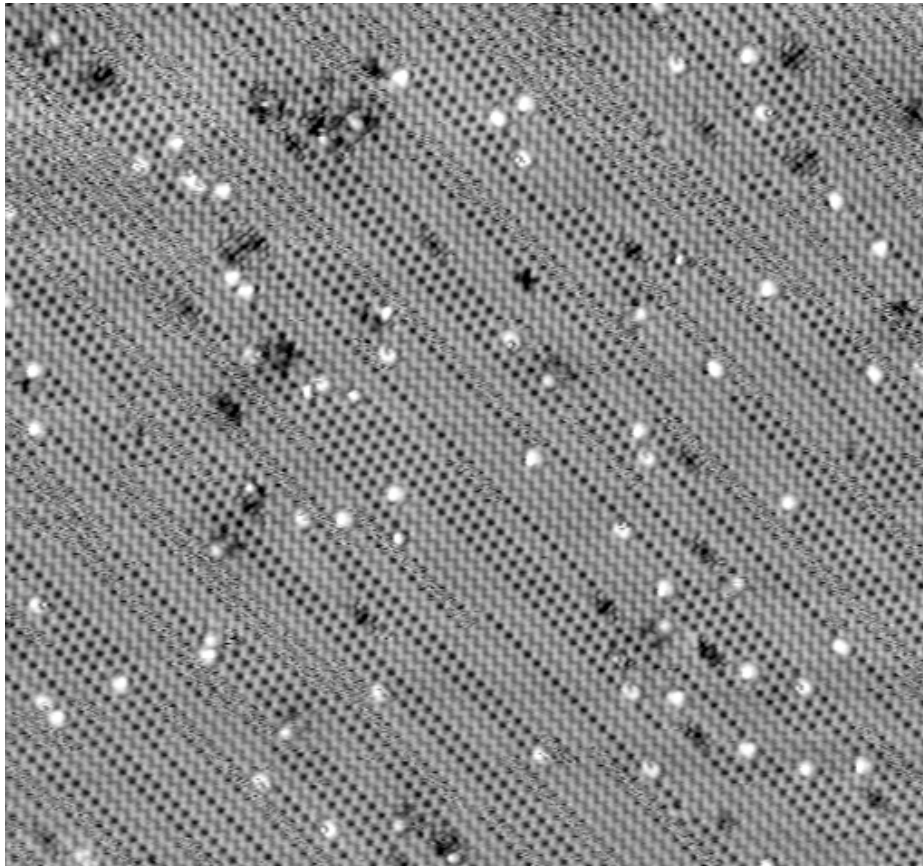


Energy window 2-3eV

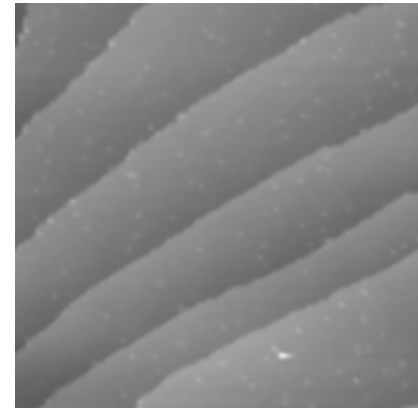


Energy window 3-4.5eV

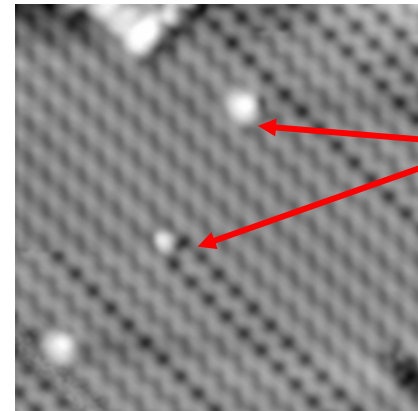
# 1,3-CHD reacted Si(100) surface at 5 K



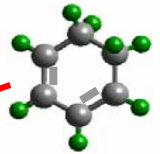
50x50 nm 100pA 700mV 5K



Pt(111) 63.5x63.5nm 0.1nA 450mV

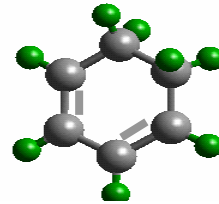
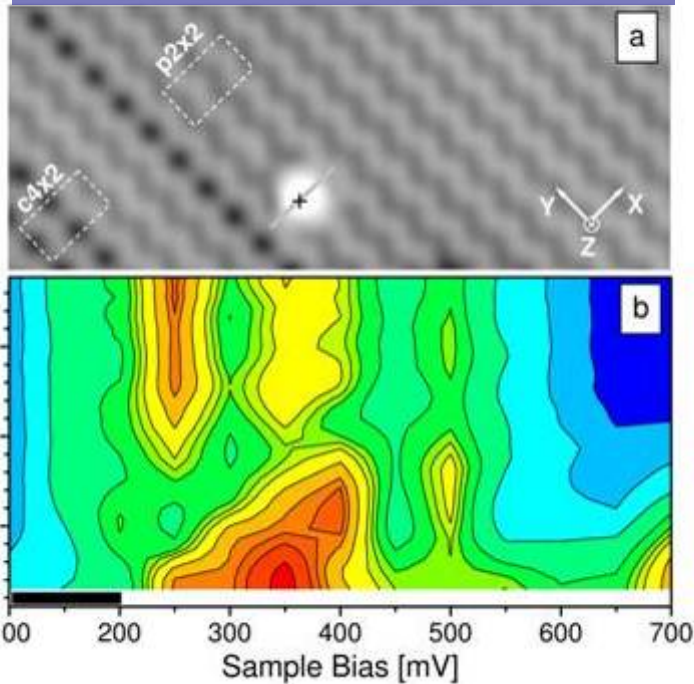


Si(100) 13x12.6nm 0.1nA 700mV



# Contacts: Single Molecule on Si(100)

## Electronic density of states

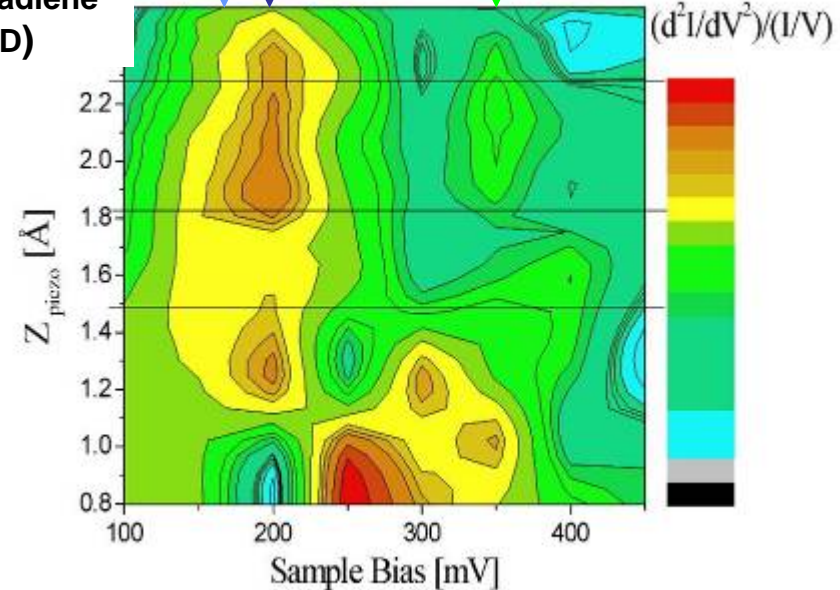


1,3-cyclohexadiene  
(1,3-CHD)

C-H bending mode

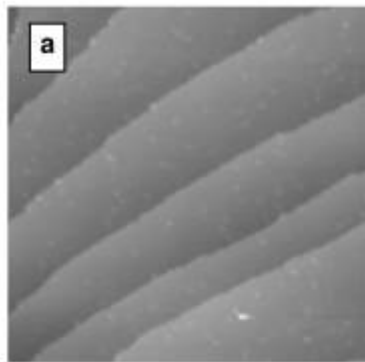
C=C stretch

C-H stretch

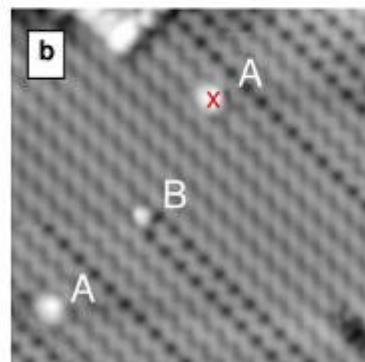


- Large LDOS feature grows in at 350meV (completely reversible) and anticorrelated with disappearance of C=C vibrations
- Bias window 0 – 200meV LDOS independent of separation (basis for subsequent relaxation and force measurements)

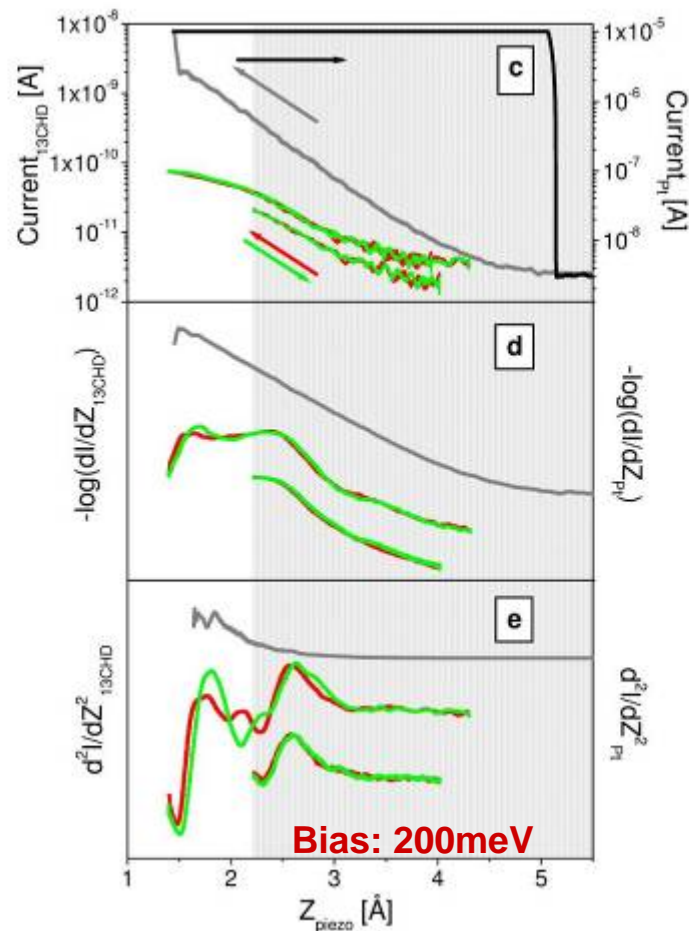
# Current during approach to contact



Pt(111) 63.5x63.5nm  
0.1nA 450mV



13CHD/Si(100) 13x12.6nm  
0.1nA 700mV



## Contact with Pt surface

Current well described by:

$$I \propto \exp(-A\sqrt{\phi_A} z) \quad (1)$$

Jump to contact & neck formation

## Contact with 1,3-CHD molecule

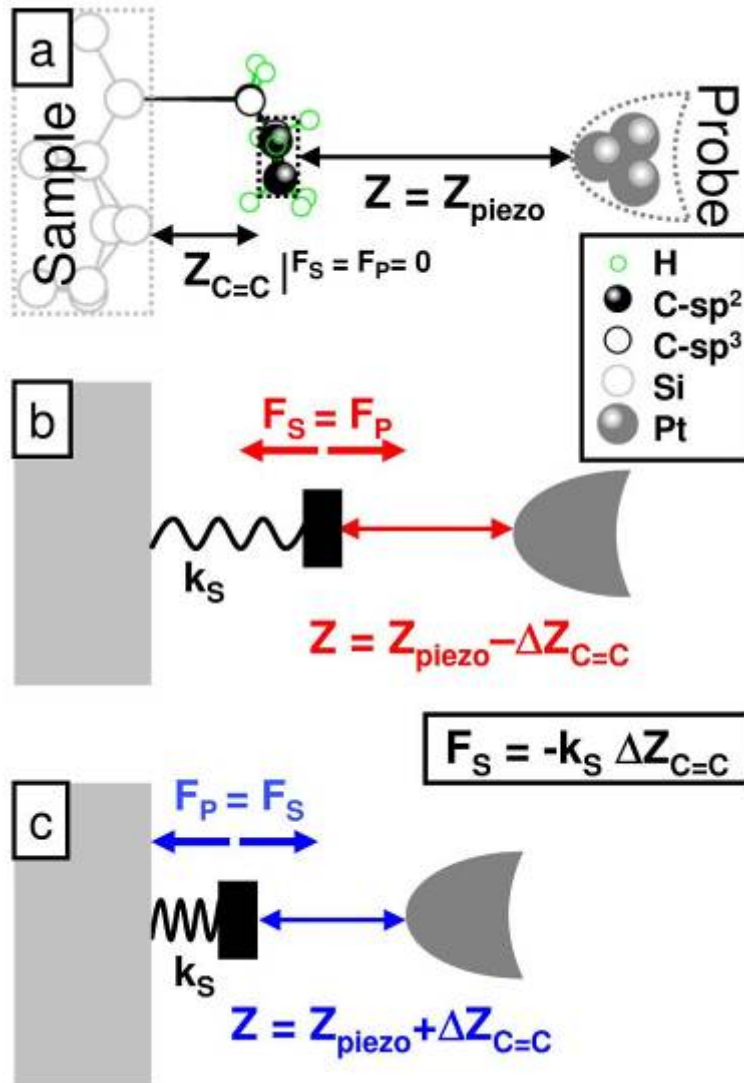
Current not globally described by Eq. (1)

Deviations seen in harmonics

Shaded region: no hysteresis

What is the origin of these deviations from Eq. (1) ?

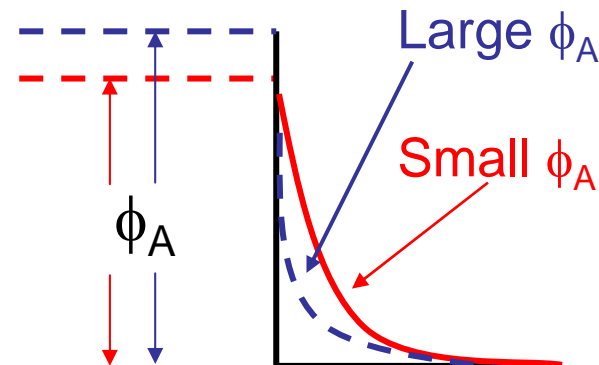
# Origin of Relaxation Interaction



$$\begin{aligned} \Delta Z_{\text{gap}} &= - (\Delta Z_{\text{piezo}} + \Delta Z_{\text{C=C}}) \\ &= - \Delta Z_{\text{piezo}} + F_P / k_S \\ &= - \Delta Z_{\text{piezo}} + \alpha F_P \end{aligned}$$

Current increase during approach deviates from  $I \propto \exp(-A\sqrt{\phi_A} z_{\text{piezo}})$

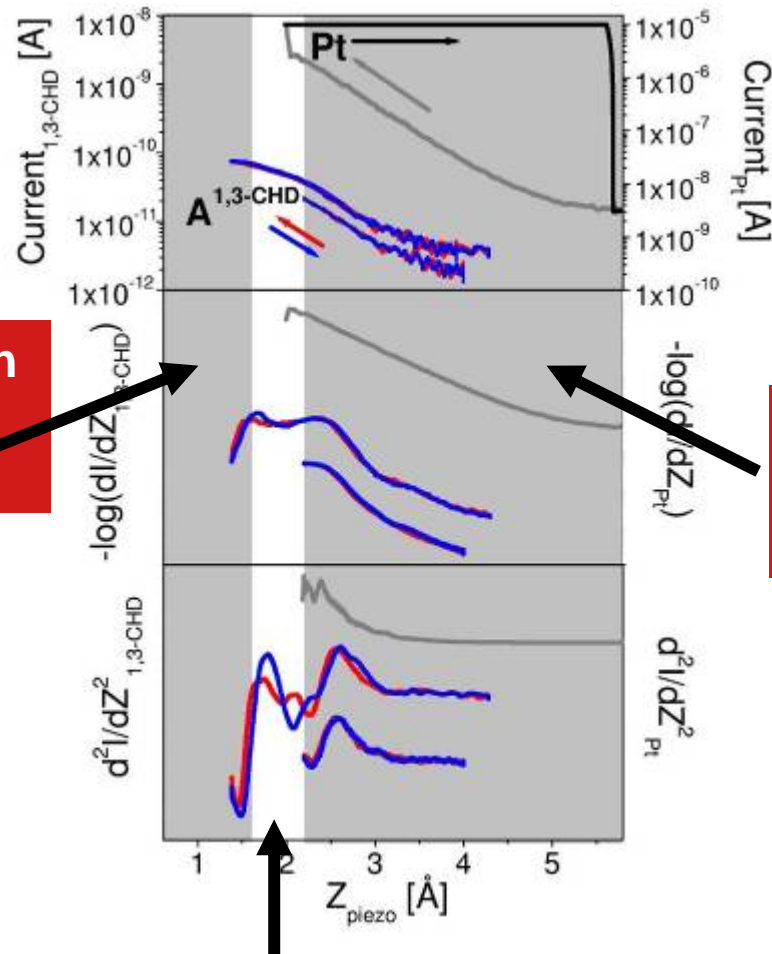
Interpreted locally as a change in the apparent barrier height  $\phi_A$





# Qualitative Analysis of Current Hysteresis

## Shaded hysteresis-free regions



Bond compression  
and relaxation  
(reversible)

Approach to  
bond formation  
(reversible)

Bond-making and breaking region (dissipative)

# Quantitative Analysis

$$F = 0$$

$$I \propto \exp(-A\sqrt{\phi}Z)$$

$$I' = \frac{dI}{dZ} \propto -A\sqrt{\phi}I$$

$$I'' = \frac{d^2I}{dZ^2} \propto A^2\phi I$$

$$\left(-\frac{I'}{IA}\right)^2 \propto \phi_{A1}$$

$$\frac{I''}{IA^2} \propto \phi_{A2}$$

$$\left(-\frac{I''}{I'A}\right)^2 \propto \phi_{A3}$$

Nominally  
identical

$$F \neq 0$$

$$I \propto \exp[-A\sqrt{\phi}(Z_{piezo} + Z_0 + \alpha F)]$$

$$I' \propto -A\sqrt{\phi}(1 + \alpha F')I$$

$$I'' \propto [A^2\phi(1 + \alpha F') - A\sqrt{\phi}\alpha F'']I$$

$$\left(-\frac{I'}{IA}\right)^2 \propto \phi(1 + \alpha F')^2$$

$$\frac{I''}{IA^2} \propto \phi(1 + \alpha F')^2 - \frac{\sqrt{\phi}}{A}\alpha F''$$

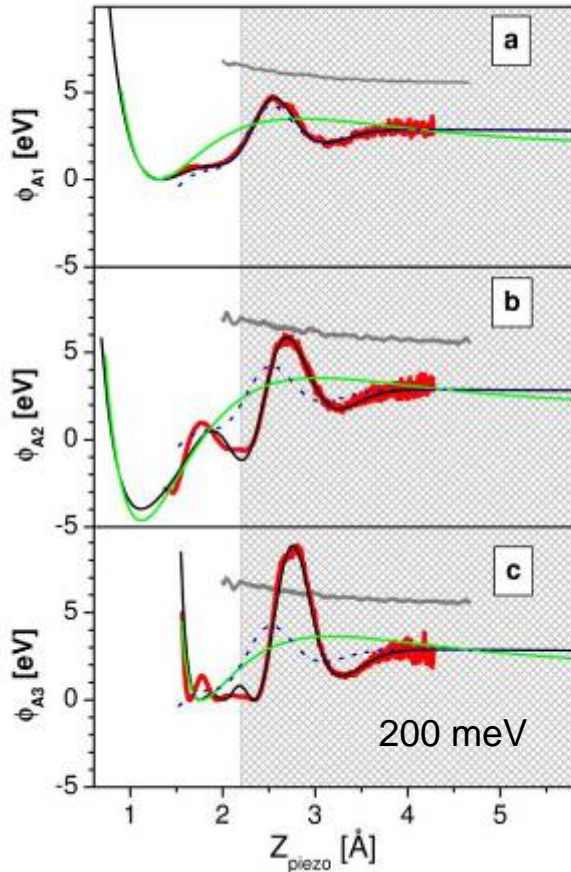
$$\left(-\frac{I''}{I'A}\right)^2 \propto \left[\sqrt{\phi}(1 + \alpha F') - \frac{\alpha F''}{A(1 + \alpha F')}\right]^2$$

Forces present: harmonics  $dI/dZ$  and  $d^2I/dZ^2$  are related to the local force gradient

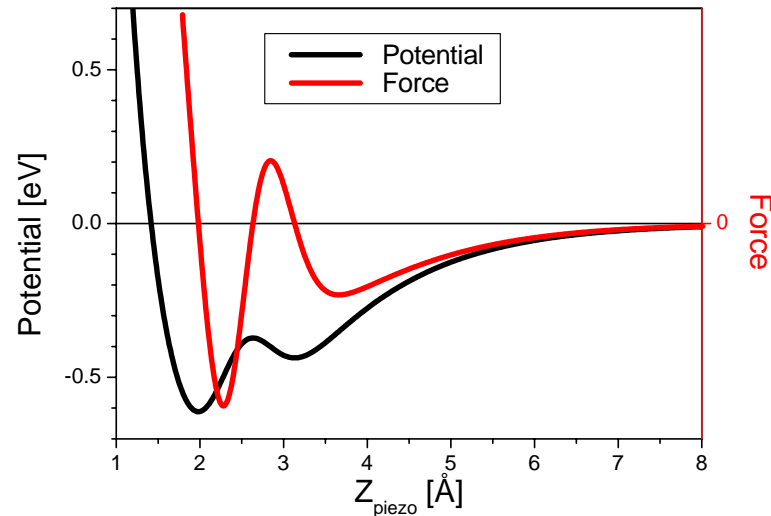


# Quantitative Analysis: Interaction Potentials

Invert current and barrier height data to determine forces & potentials



— Morse potential  
— Morse + Gaussian barrier  
- - - Force gradient



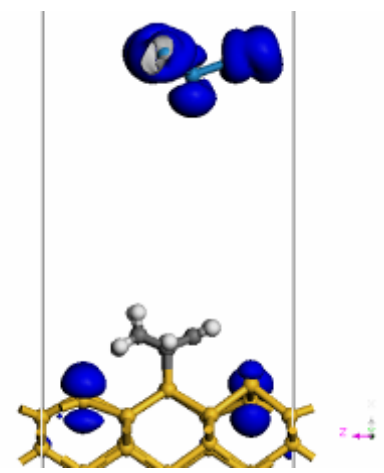
Description of the  $\phi$  data requires a barrier term

## Questions:

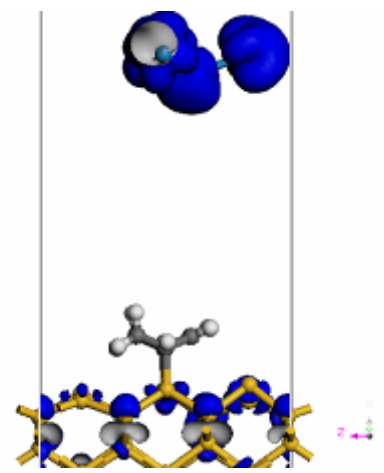
1. Is the well depth meaningful?
2. What is the origin of this barrier?

} Use DFT

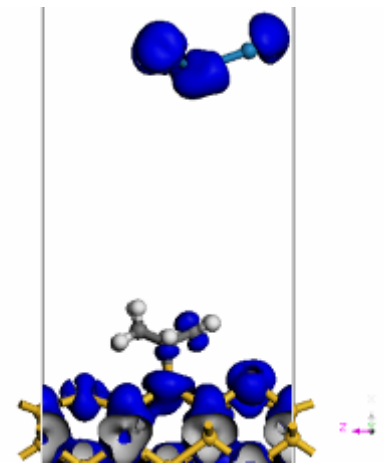
# Emergence of LDOS feature



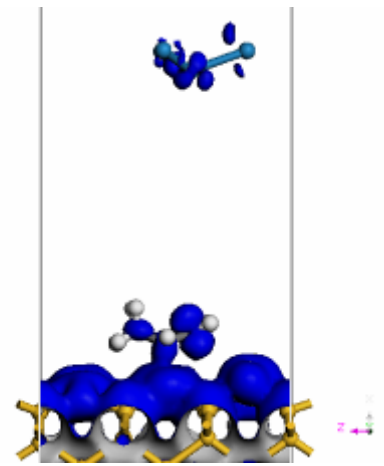
Energy window 0-1eV



Energy window 1-2eV

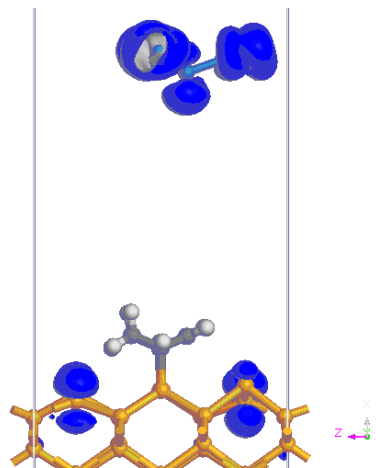


Energy window 2-3eV

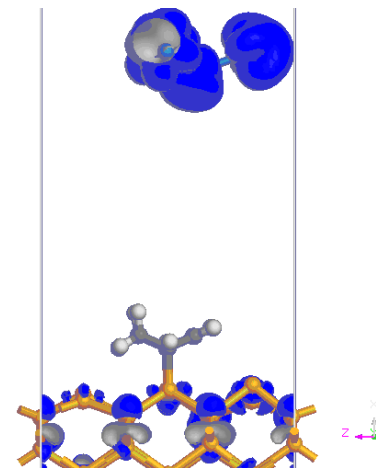


Energy window 3-4eV

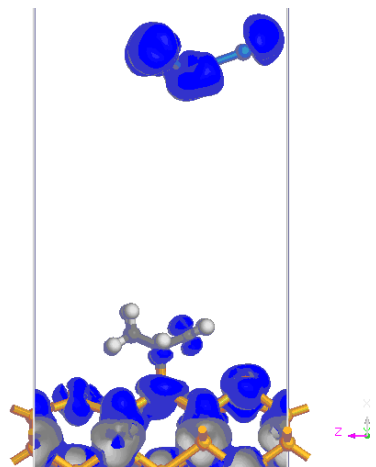
# DOS in the presence of the probe tip



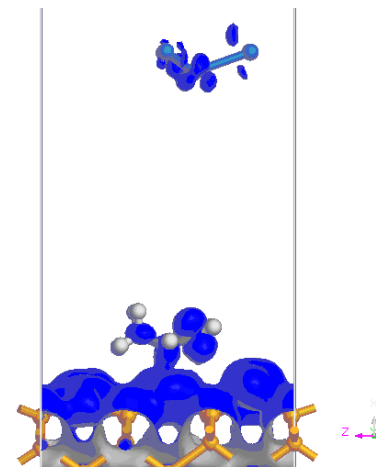
Energy window 0-1eV



Energy window 1-2eV



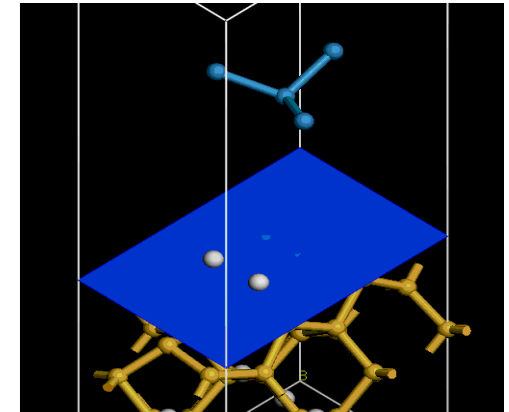
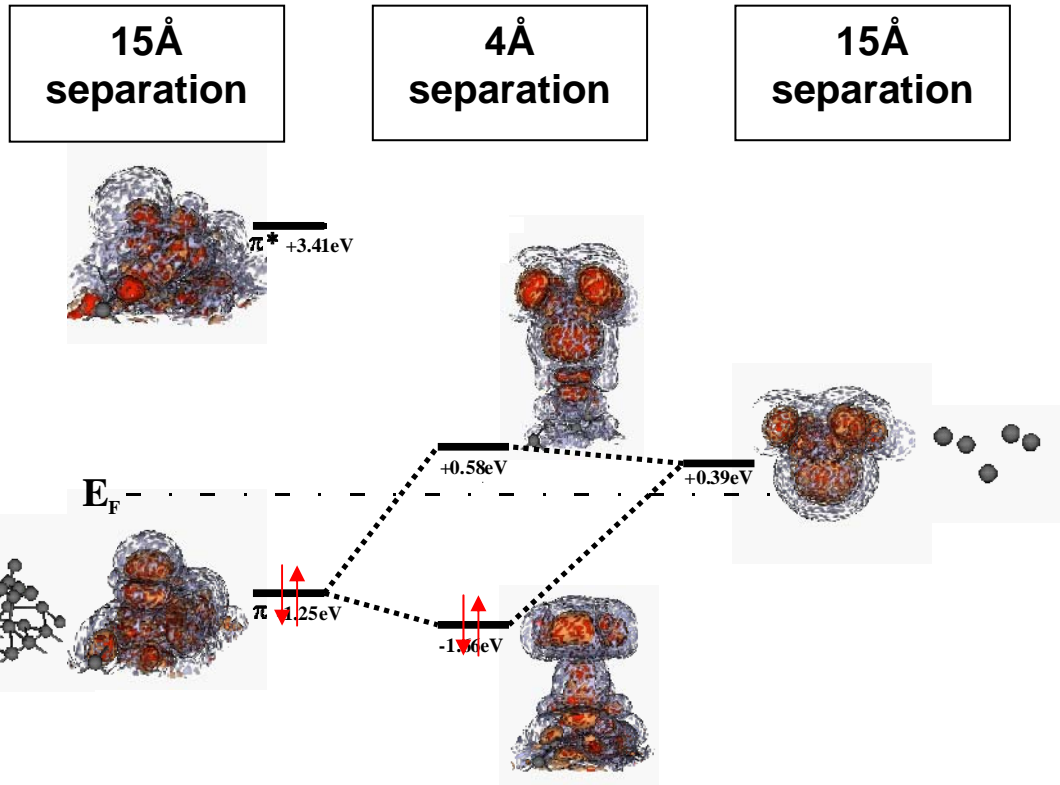
Energy window 2-3eV



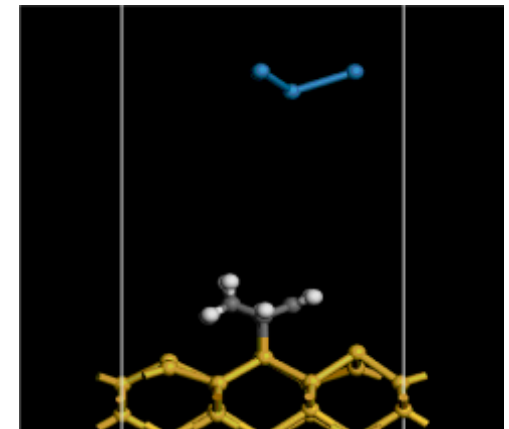
Energy window 3-4eV

Interaction of probe with C=C bond upon contact yields interface state in 0 – 1eV

# Origin of Interface State



$\int$  LDOS (0-1.5 eV) ~ STM image

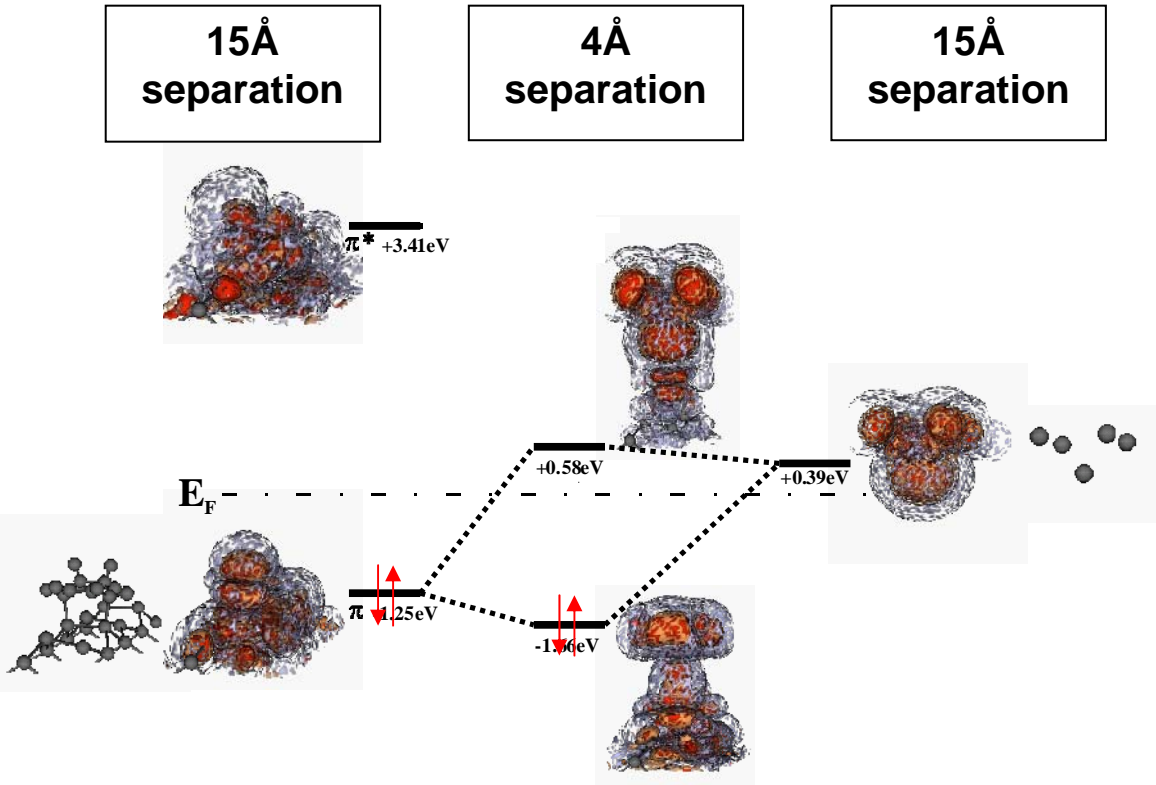


Tip above C=C

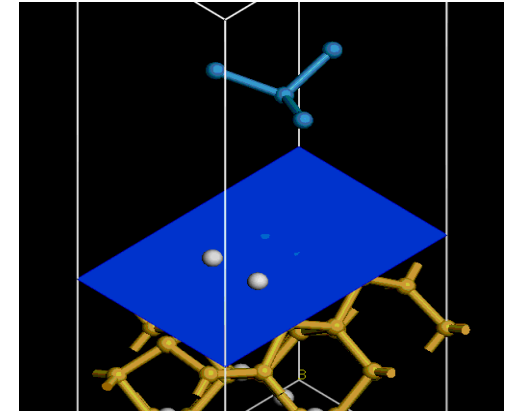
Bonding interaction associated with  $p\pi \rightarrow d\pi$   
charge transfer from C=C to Pt apex atom

**Molecule conductance dominated by interface  
state which is responsible for STM image**

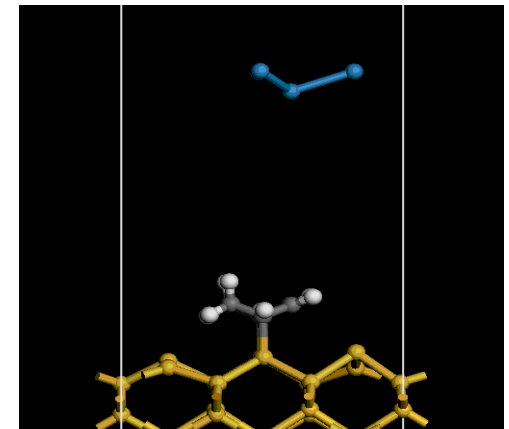
# Origin of Interface State



DFT also observes barrier - due to deformation and rehybridisation of the molecule C=C bond



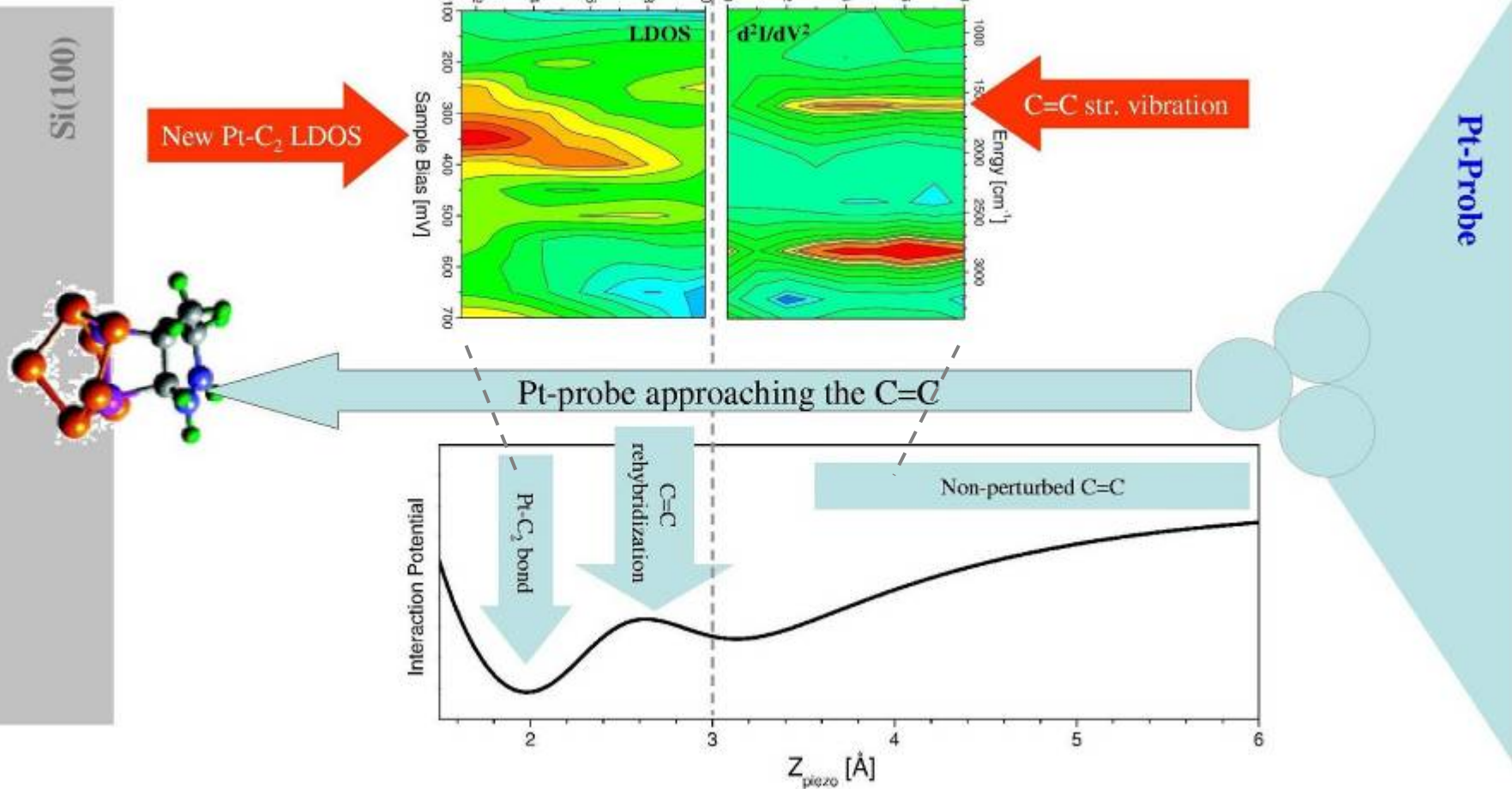
Tip approach: Interface state



Deformation of molecule

# Comprehensive picture of contact bond formation <sup>24</sup>

1,3-C<sub>6</sub>H<sub>8</sub> Si(100) dimer



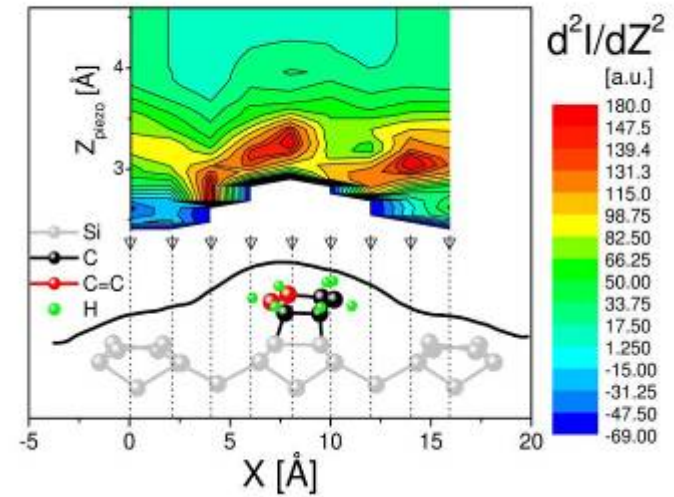
Track dynamics of contact formation Precise overlay of potential, electronic and vibrational properties

*NANO LETTERS* 6(9) 2006; *PRL* 97, 098304, 2006.



# Conclusions: Molecular Contacts

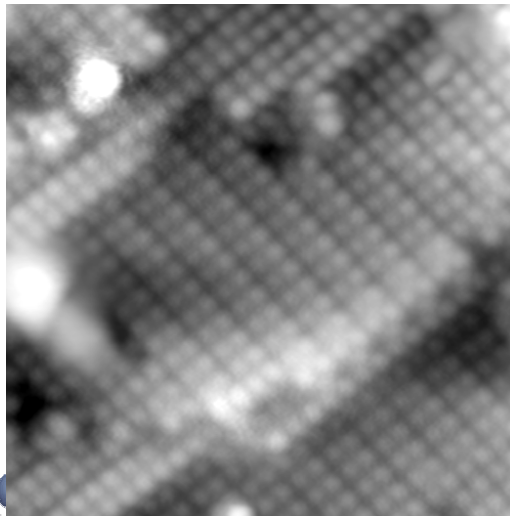
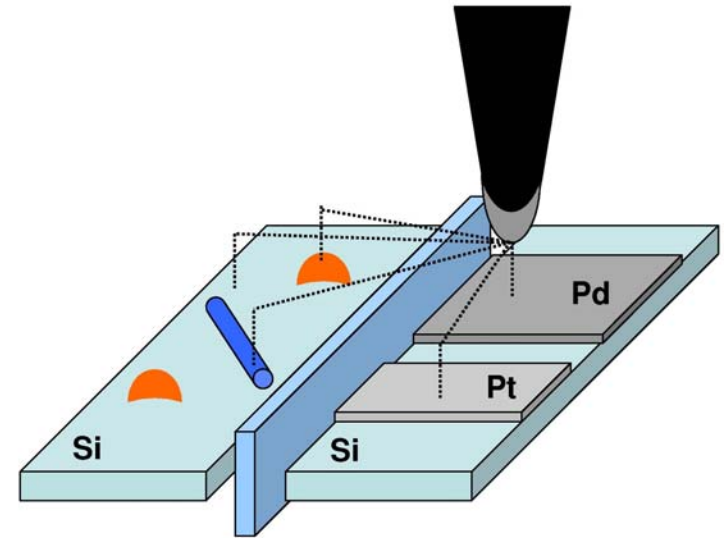
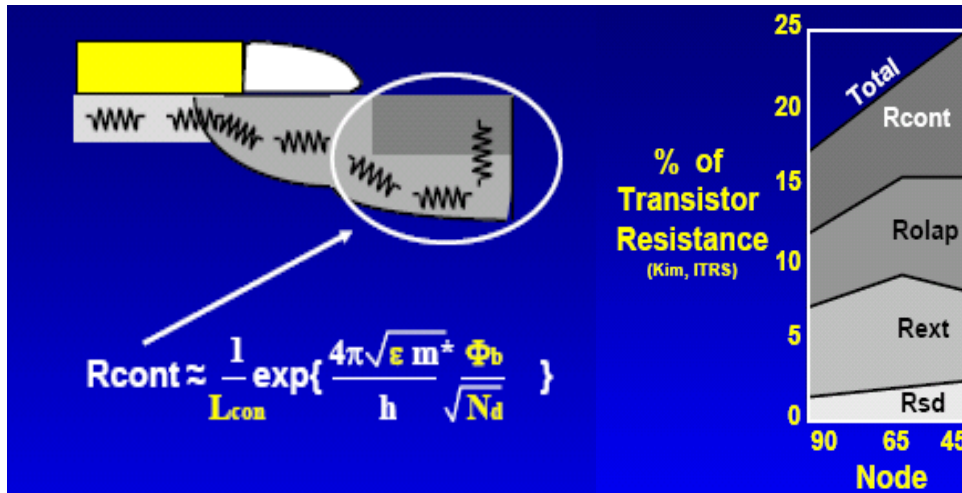
- Three types of current-approach curves
  - Smooth exponential increase (tunnelling)
  - Sharp jumps (local atomic motion)
  - Slow, reproducible change in slope (relaxation forces)



*Relaxation map of single 1,3 CHD*

- Interface states may provide route to tailor molecule transport properties
- Track actual formation of contacts (chemical bond formation, evolution of vibrations, actual measure of potential)
- Widely applicable; catalysts and studies of general reaction dynamics

# Example B: Nanoscale contact with Si(100):H

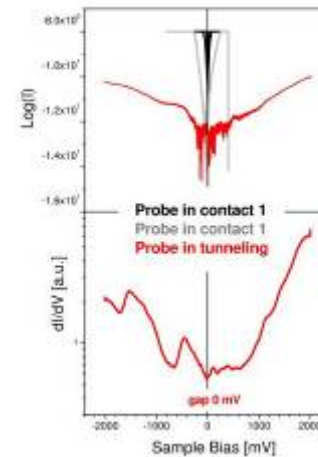
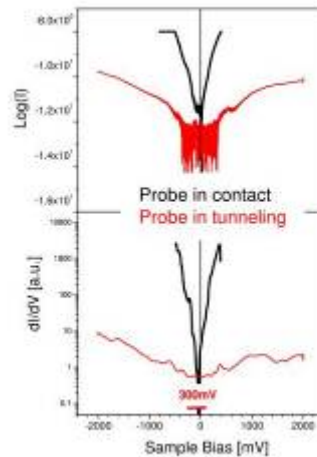
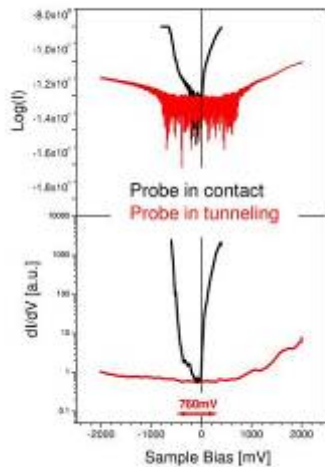
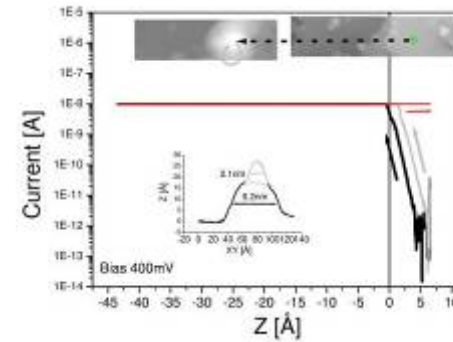
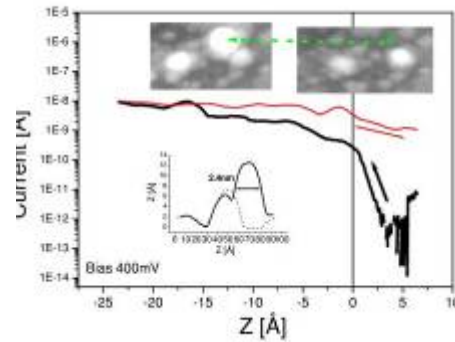
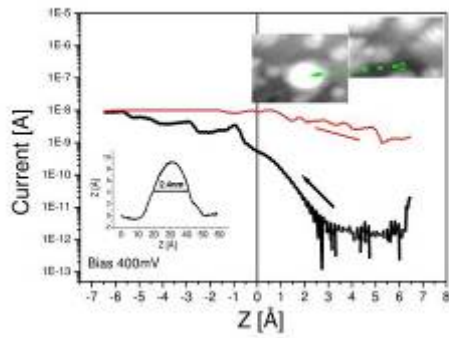


Si(100):H passivated

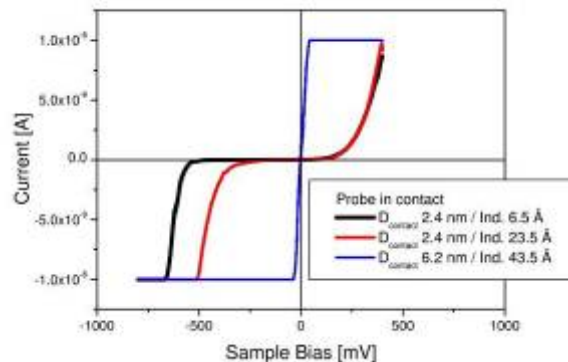
**Specific Problem:** contact resistance between contact metal and n+ region at source and drain limiting device performance

**Approach:** study of controlled contact formation at 5K. Measure local forces, electronic density of states and vibrations simultaneously

# Pd Nanocontacts on n+ Si(100):H

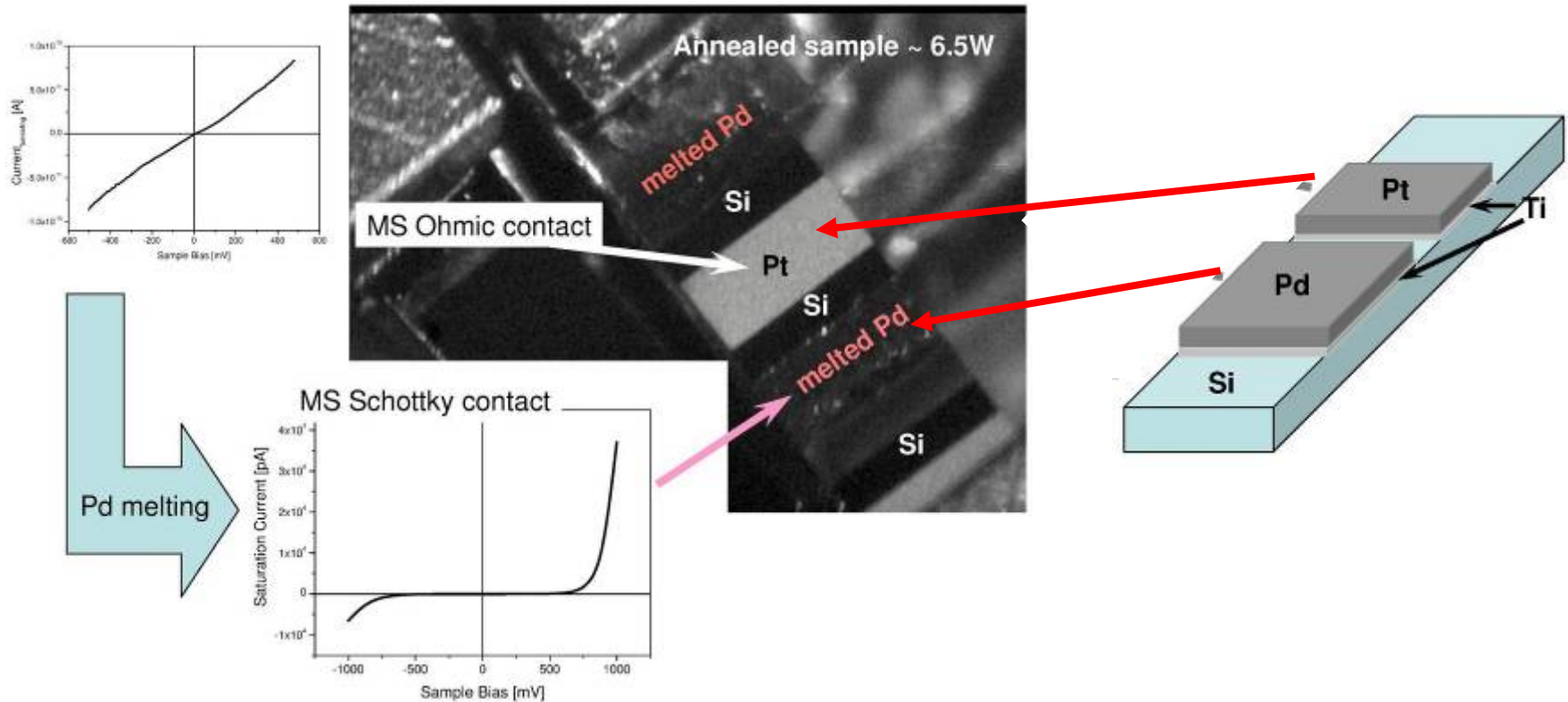


Ohmic behaviour observed even with tunnelling contact – not an E-field point contact effect

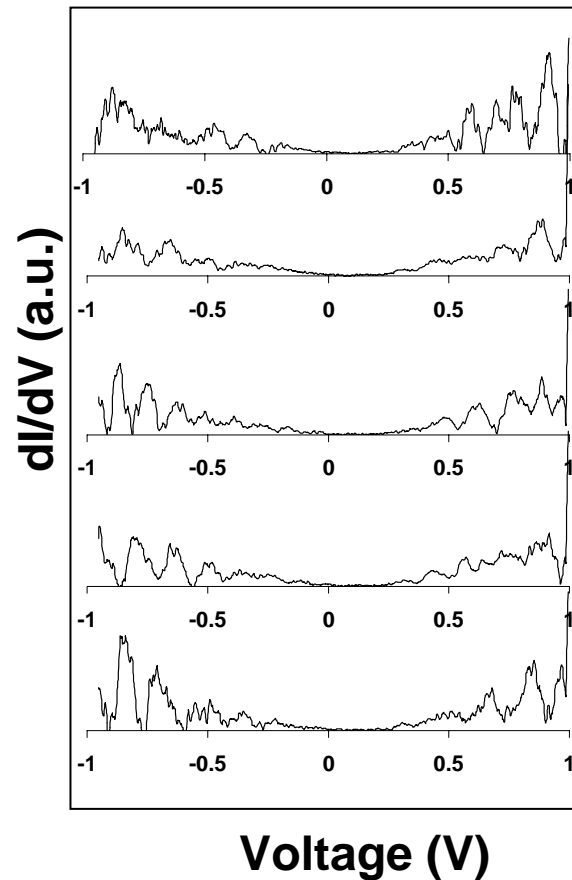
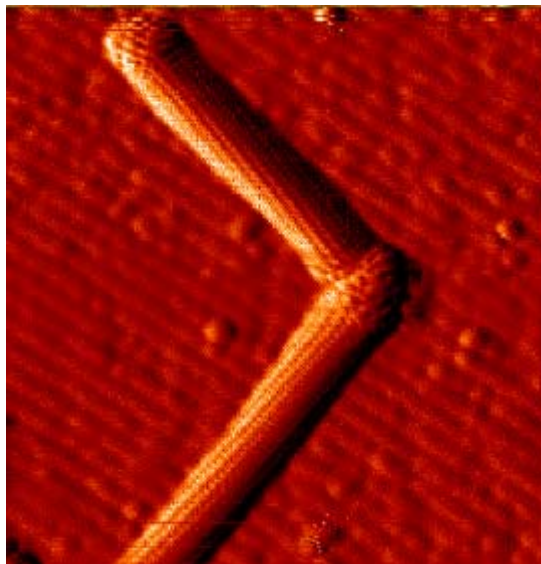
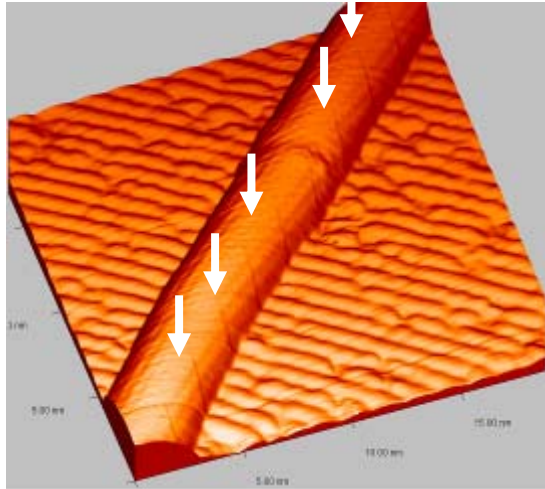


Control of the electrical contact  
 $D_{\text{contact}}$  from 2 to 7 nm shift from non-ohmic to ohmic behaviour  
 No evidence for Schottky barrier

# Macroscopic Pd:Si(100) Contacts



# Measurements on Carbon Nanotubes



**Well defined van Hove singularities**  
**RT study – peak broadening**  
**No contact studies at 5 K yet**

# CRANN Nanoscience Centre & Industry Partners



# Acknowledgements

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